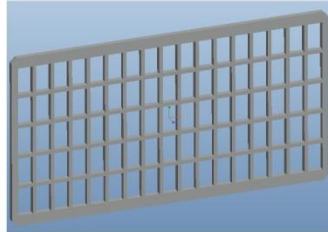


## CLEANING STANDARD



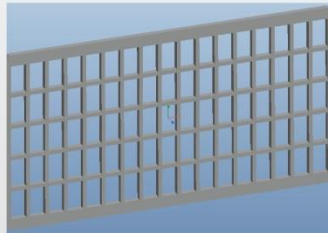
OPEN Mask



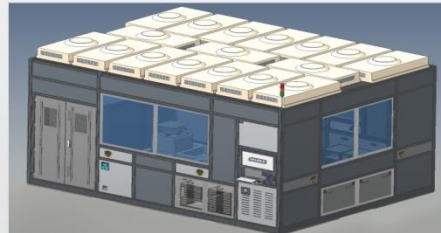
Mask Cleaner

<p><b>1. Mask Cleaning</b></p>	<p>Cleaning Process is to remove the particle of new mask and deposition material on the OPEN Mask for OLED Cathode Deposition Process.</p>
<p><b>2. Mask Cleaning Method</b></p>	<p>Deposition Material was removed by chemical and then after inspecting the surface for it, inspect Deposition Material of Cleaning Conditions.</p>

## INSPECTION STANDARD



OPEN Mask



Inspection

<p><b>1. Mask Testing Purpose</b></p>	<p>inspects Deposition Organic matter on Mask and Clean it. After Cleaning Mask, inspects that Masks condition is available.</p>
<p><b>2. Mask Inspection Method</b></p>	<p>Inspects remaining deposition material, damage and transform before scurb(Cleaning). after that, checks the status again.</p>